

Front-end CMOS Application Specific Integrated Circuits (ASICs) for Light and Charge Readout

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September 22, 2023

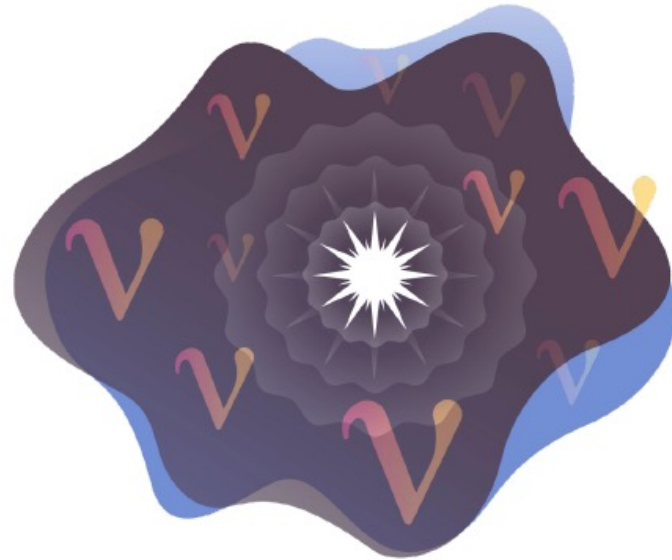


Designed for DUNE : Deep Underground Neutrino Experiment

Primary science goals



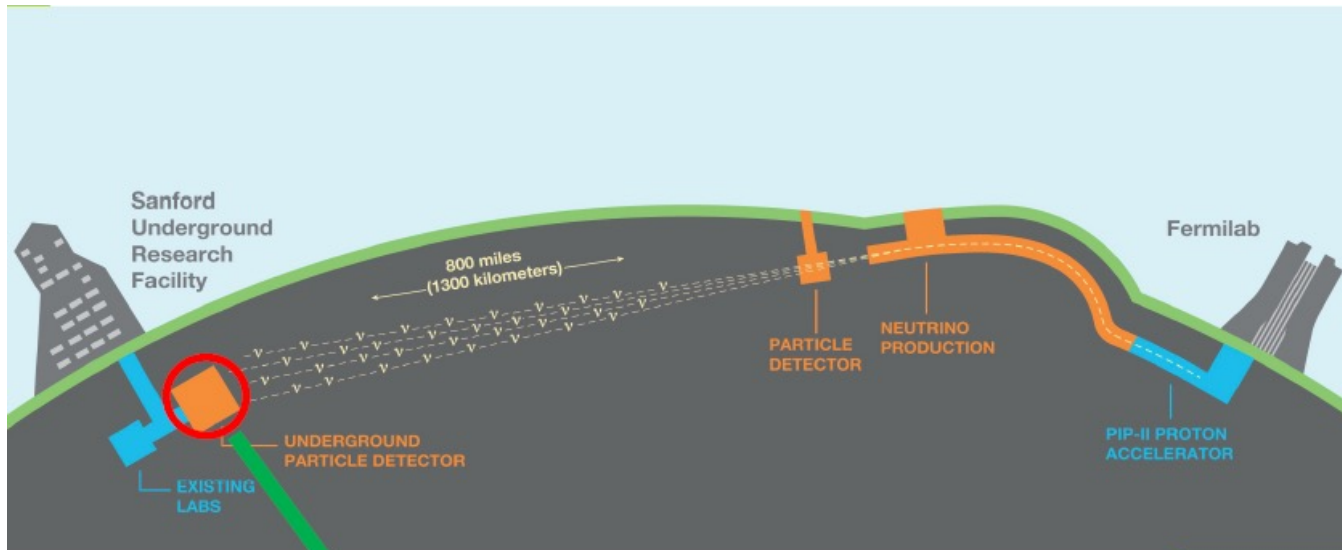
Study neutrino/antineutrino oscillations



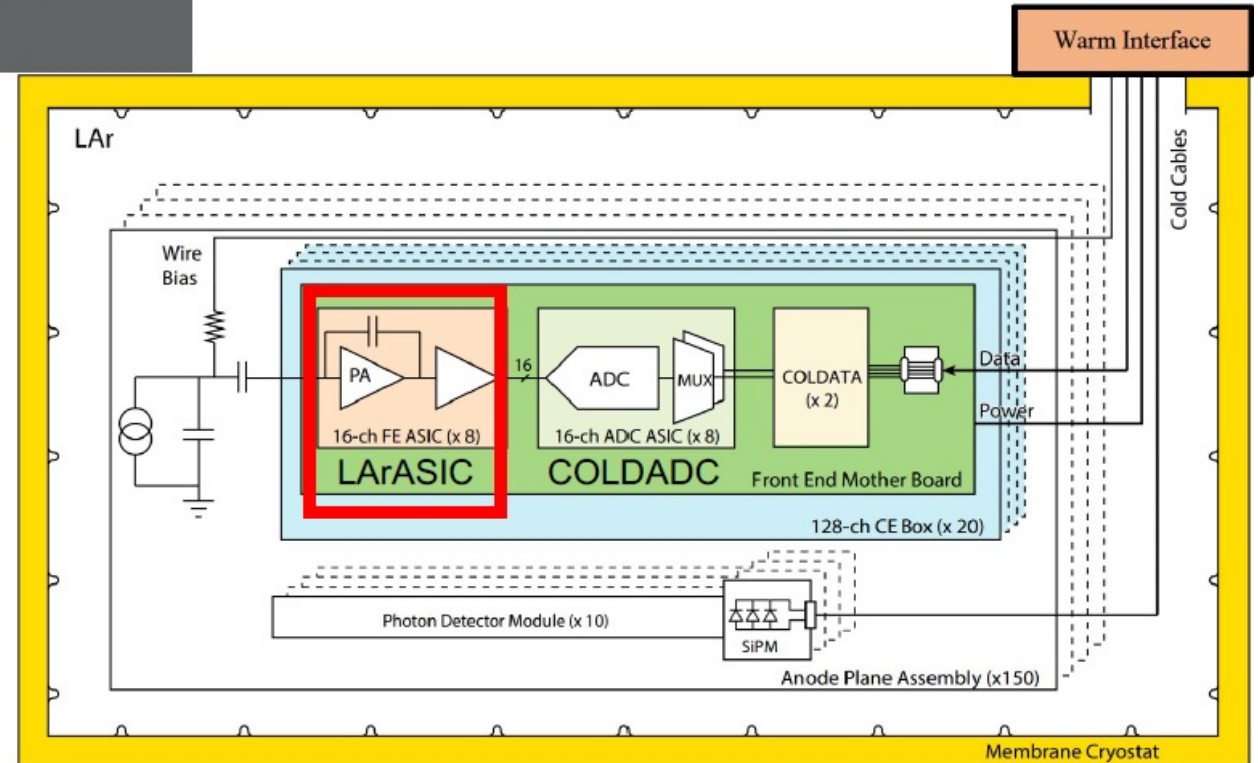
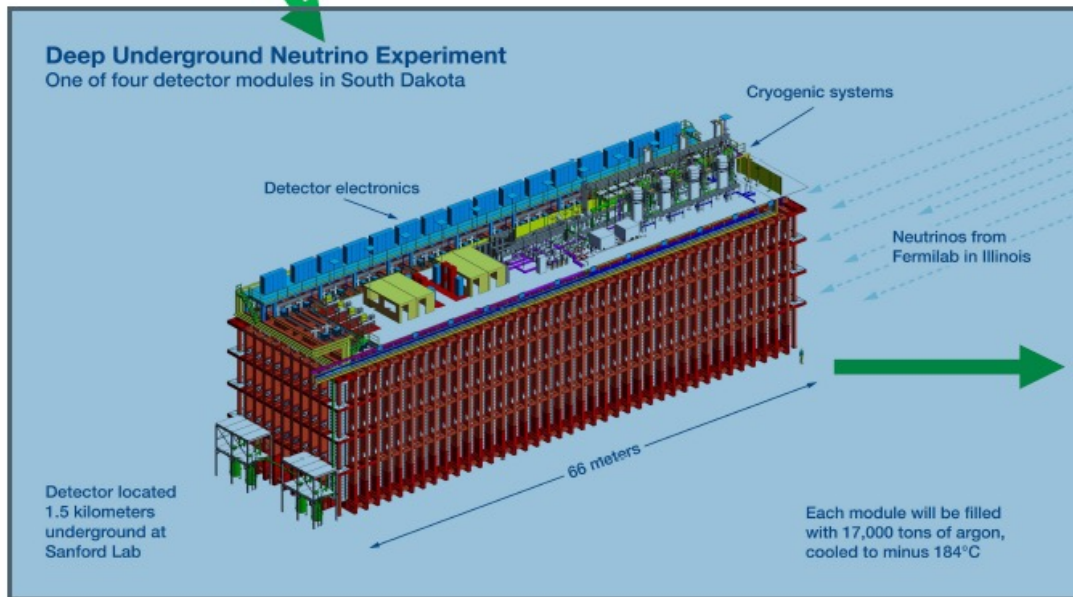
Detect neutrinos emerging from exploding stars



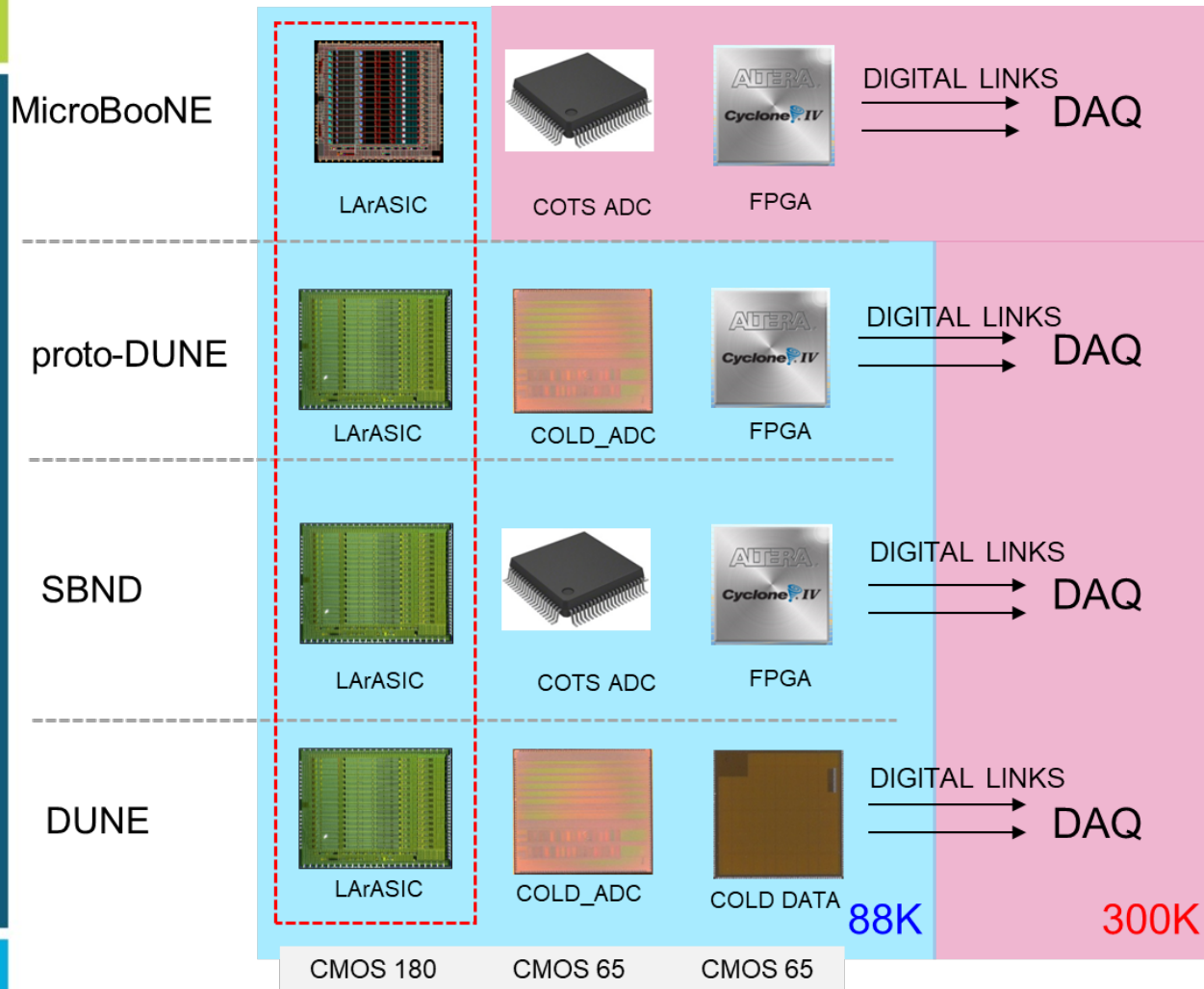
Search for signs of proton decay



- Currently deployed for readout at the Single-Phase (SP) Liquid Argon (LAr) Time-Projection Chamber (TPC) for Far Detector (FD)
- 3-chip solution for energy measurement, includes: charge amplification, shaping, digitization and serial readout
- Front-end (FE) electronics close to the detector enables readout at low-noise
- Need to ensure FE operates reliably at 87 K



Status of ASICs in DUNE



3 ASICs vs. 1 ASIC solution:

- Initially two readout options were proposed:
 - 3 ASICs vs. 1 ASIC (idea of building 1 ASIC, combining FE/ADC/transmission brought in 2016 and included as parallel path of development)
- Evolutionary development MiCroBooNE → DUNE led to the 3 ASIC solution that:
 - Helped perfect the FE (through multiple iterations)
 - Allowed debugging (procedure for ADC calibration)
 - Allowed optimization

LArASIC – status

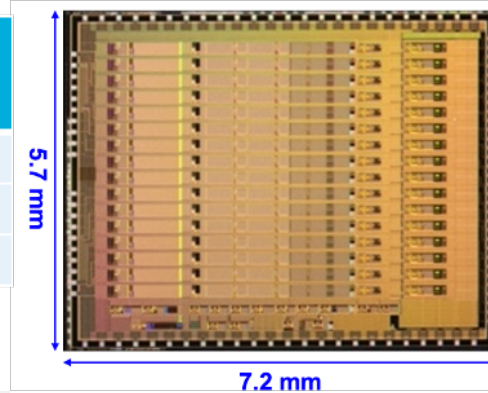
LArASIC MPW met all the DUNE requirements → fabricated ~1800 P5 and 1800 P5B (180 nm) chips (eng. run) for ProtoDUNE II

LArASIC Chips	Temp.	Tested Chips#	Good # (All channels are normal)	Yield
P5	RT	49	49	100 %
P5B	RT	1642	1635*	~99.57 %
P5B	LNT	317	317	100 %

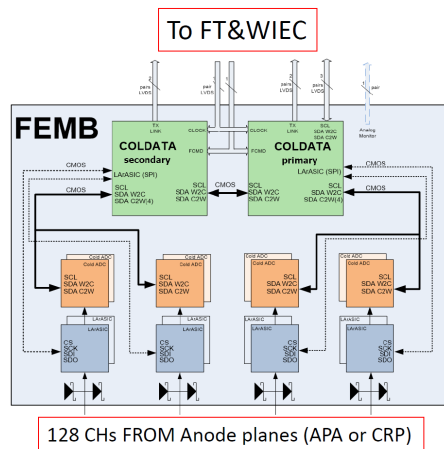
P5B has improved input ESD protection compared to P5

*Only 1 out of 16 channels in each of the two chips are non-functional

>6 months ago, now more statistics is available

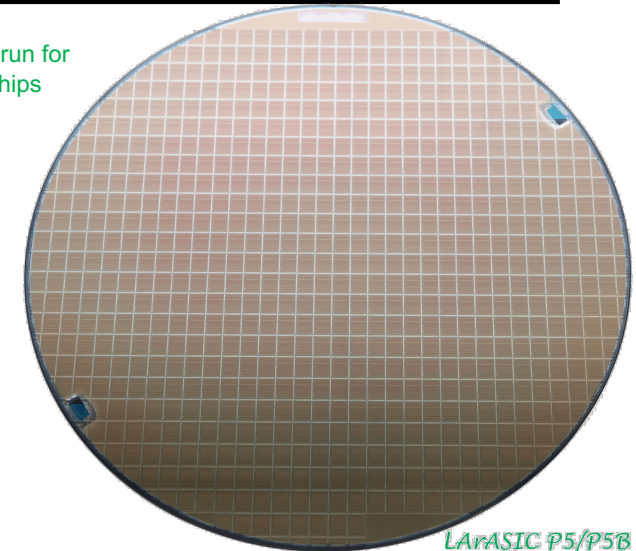


LArASIC performance with differential interface



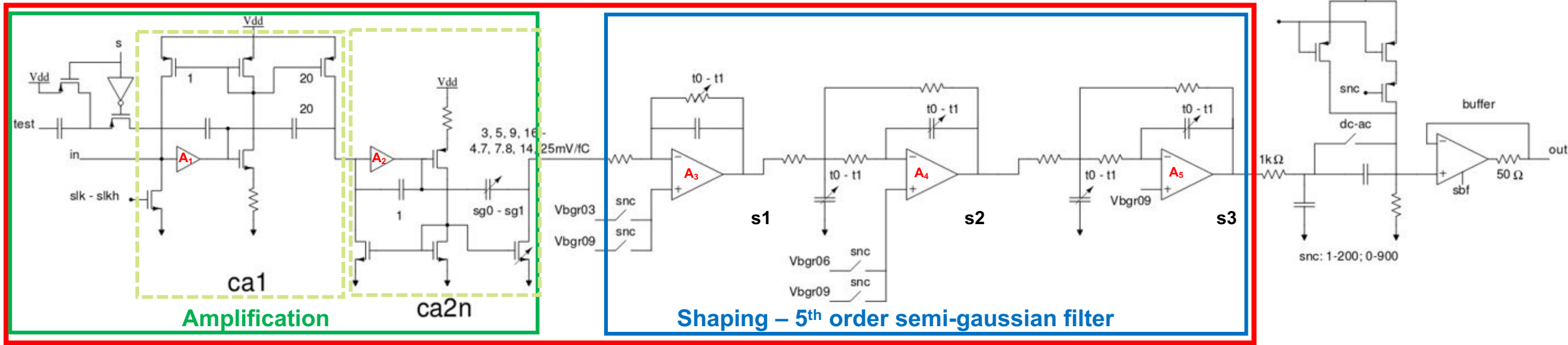
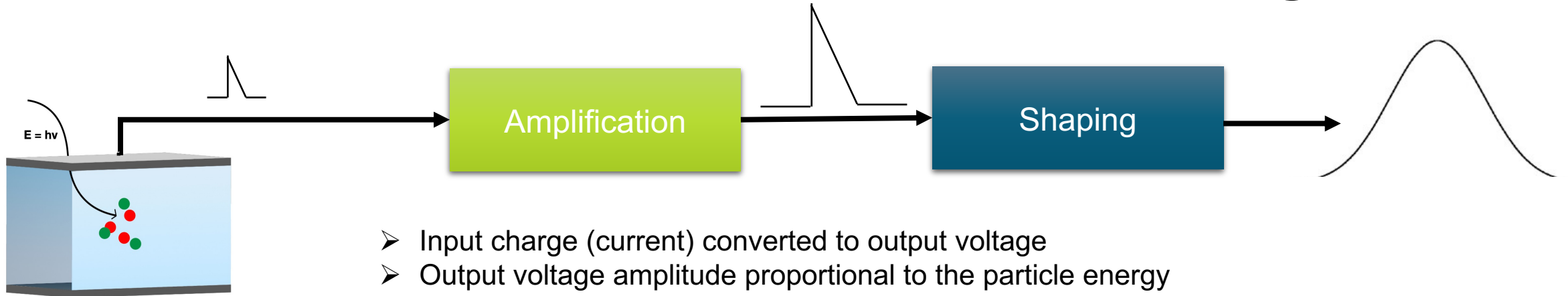
250 wafers LArASIC production run for DUNE 75k P5 and 75k P5B chips

Design currently being translated to 65 nm CMOS

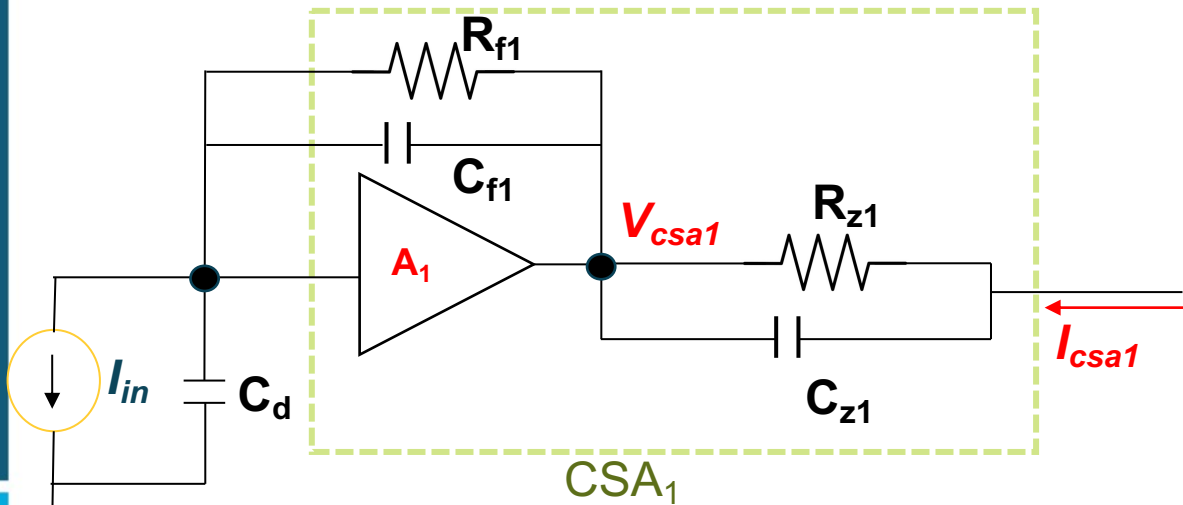
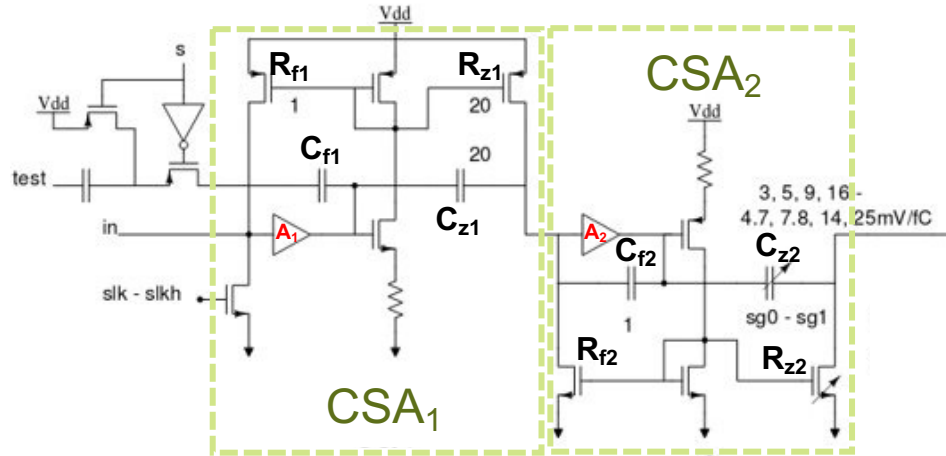


8" wafer with 610 LArASICs P5 and P5A(B) w. increased ESD protection

LArASIC architecture / circuit topologies



Charge Sensitive Amplifier design

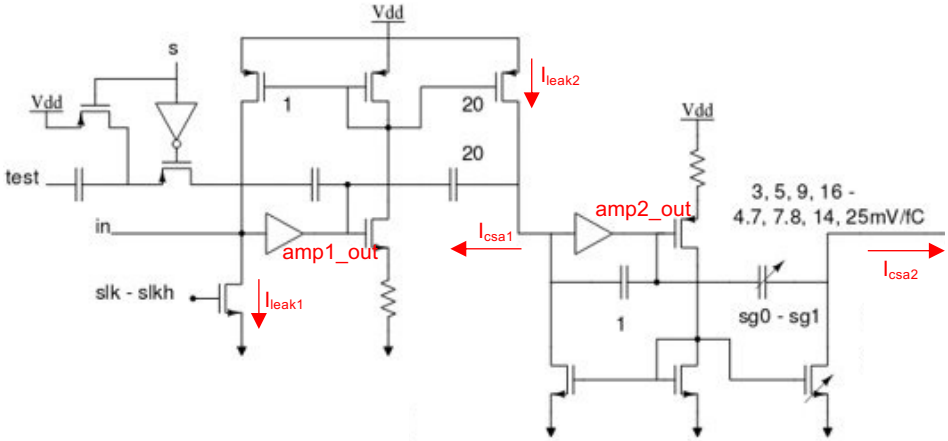


- Charge amplifiers use current-mirror based adaptive continuous reset
- A_1 and A_2 : 3-stage amplifiers (> 100 dB gain)
- Pole zero cancellation ($C_f R_f = C_z R_z$) ensures fast I_{csa1} pulse and prevents baseline drift

$$I_{csa1}(s) = I_{in}(s) \underbrace{\frac{R_{f1}}{(1 + sC_{f1}R_{f1})} \frac{(1 + sC_{z1}R_{z1})}{R_{z1}}}_{V_{csa1}}$$

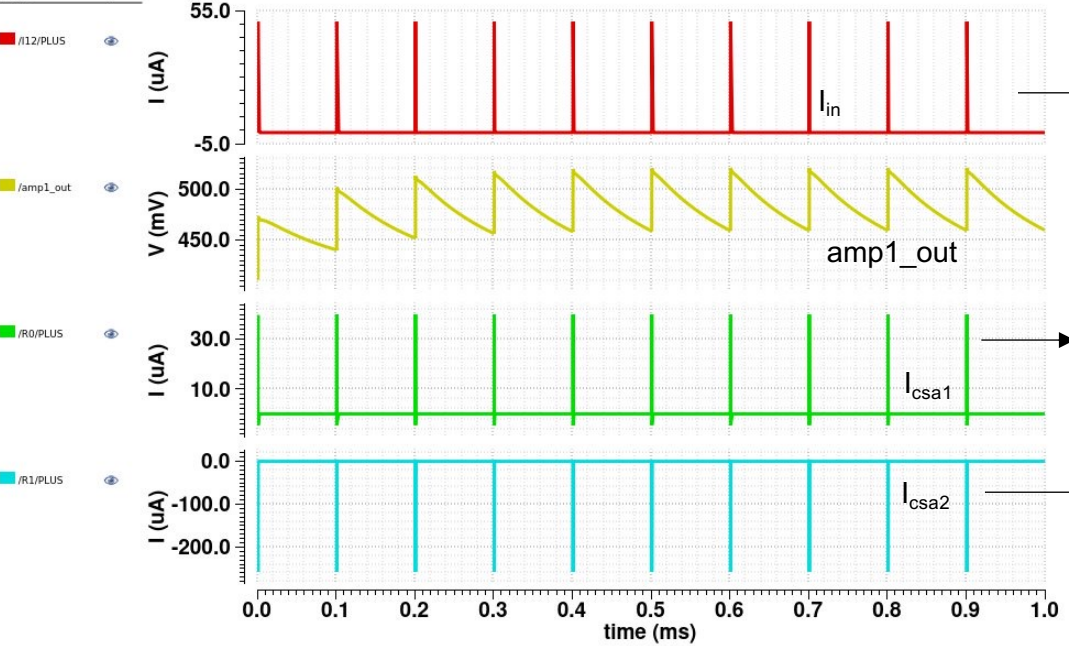
- $C_{z1} = 20C_{f1}$, $R_{z1} = (1/20)R_{f1}$, charge gain provided by $CSA_1 = 20$
- $C_{z1} = (3 \text{ or } 5 \text{ or } 9 \text{ or } 16)C_{f1}$, $R_{z1} = (1/3 \text{ or } 1/5 \text{ or } 1/9 \text{ or } 1/20)R_{f1}$, charge gain (programmable) provided by $CSA_2 = 3 \text{ or } 5 \text{ or } 9 \text{ or } 16$

CSA₁ and CSA₂ charge multiplication check



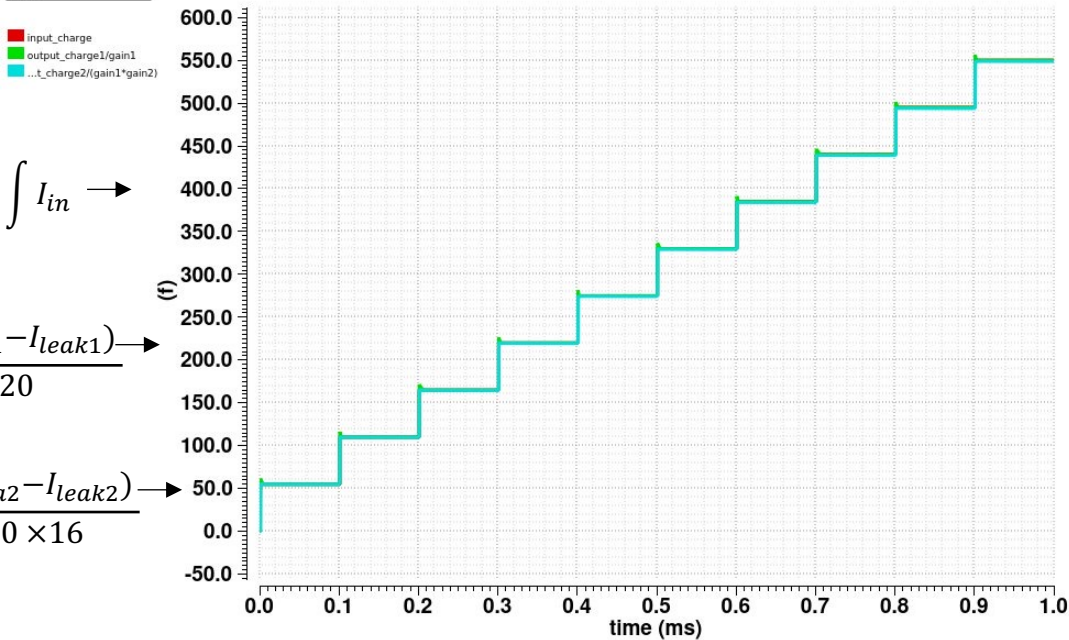
Transient Response

Name ...



input_charge:output_charge1/gain1:output_charge2/(gain1*gain2)

Name

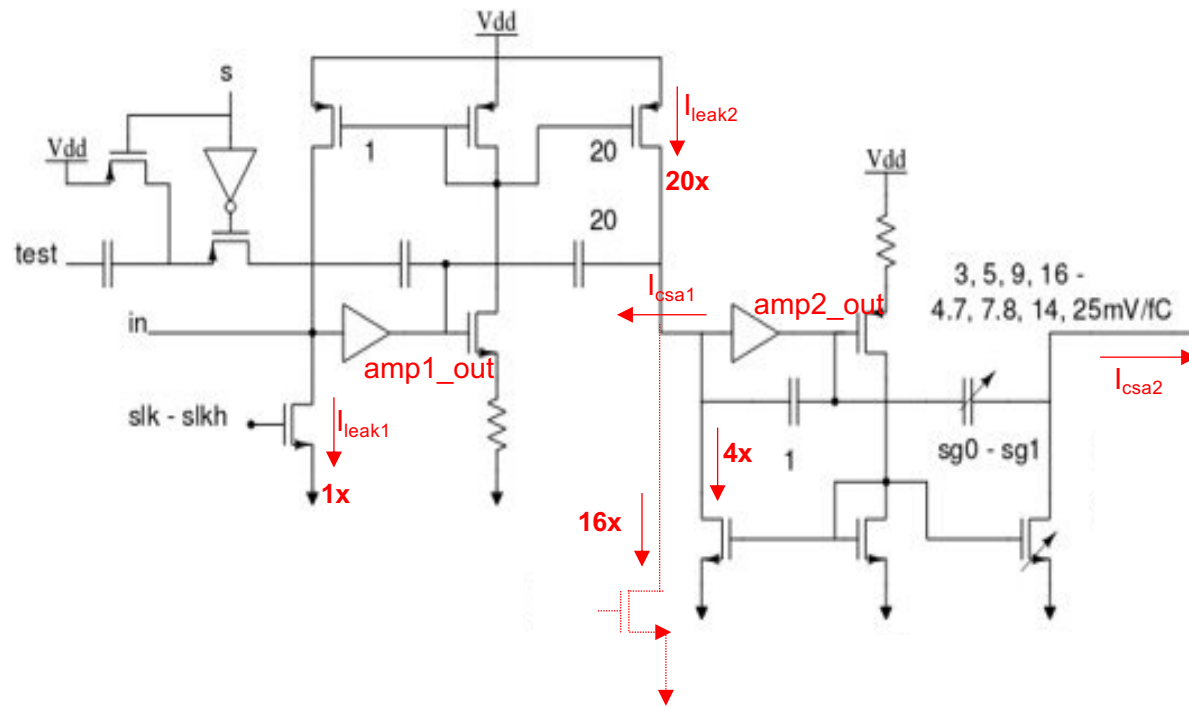


$$\int I_{in}$$

$$\frac{\int (I_{csa1} - I_{leak1})}{20}$$

$$\frac{\int (I_{csa2} - I_{leak2})}{20 \times 16}$$

CSA₂ reset (leakage) current subtraction



- Reset Quiescent Current (RQI) subtraction for CSA₂ to be implemented in the new design
- Prevents propagation of leakage current and corresponding baseline shift
- To be made programmable independently for each channel

Gain and bandwidth comparisons for amplifiers

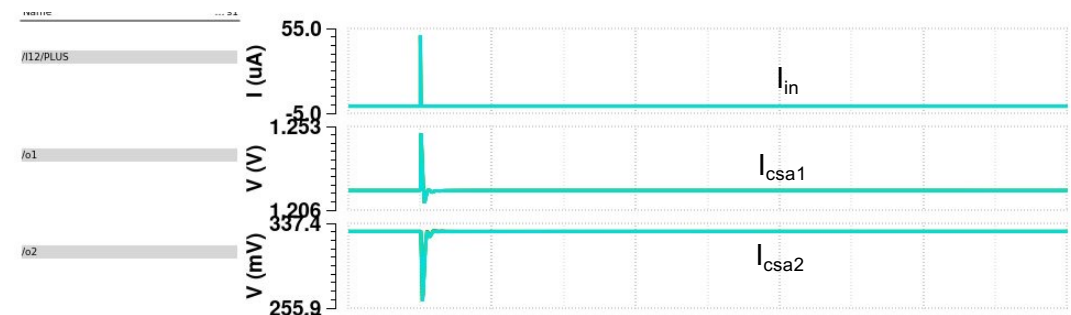
A ₁		
	Gain	Bandwidth
180 nm	93 dB	4 MHz
65 nm	113 dB	10 MHz

- Higher amplifier gain => more precise current multiplication
- Higher amplifier bandwidth => faster output response

A ₂			
	Setting	Gain	Bandwidth
180 nm	4.7 mV/fC	104 dB	42 MHz
	7.8 mV/fC		31 MHz
	14 mV/fC		21 MHz
	25 mV/fC		14 MHz
65 nm	4.7 mV/fC	114 dB	56 MHz
	7.8 mV/fC		45 MHz
	14 mV/fC		32 MHz
	25 mV/fC		22 MHz

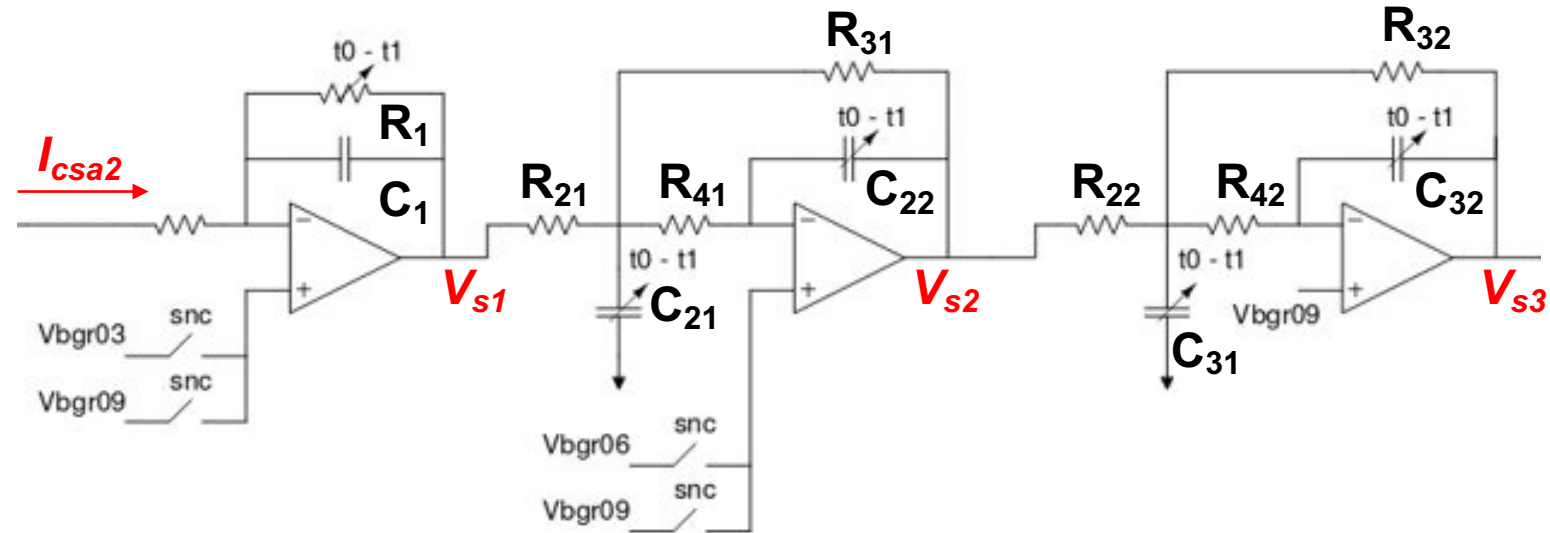


180 nm



65 nm

Shaper design



- Implemented shaper is a 5th order semi-gaussian filter with complex conjugate poles
- V_{csa2} output is a fast pulse, poses stringent requirements on peak capturing circuit (must be fast and accurate)
- Shaper slows down the variations near signal peak
- (Nearly) equal rise and fall times maximize the output signal amplitude for a given pulse duration

$$V_{s1}(s) = I_{csa2}(s) \frac{R_1}{(1 + sC_1R_1)}$$

$$V_{s2}(s) = V_{s1}(s) \frac{1}{s^2 + s \left(\frac{1}{R_{21}C_{21}} + \frac{1}{R_{31}C_{31}} + \frac{1}{R_{41}C_{21}} \right) + \frac{1}{R_{31}R_{41}C_{21}C_{31}}}$$

$V_{s3}(s)$ is similar.....

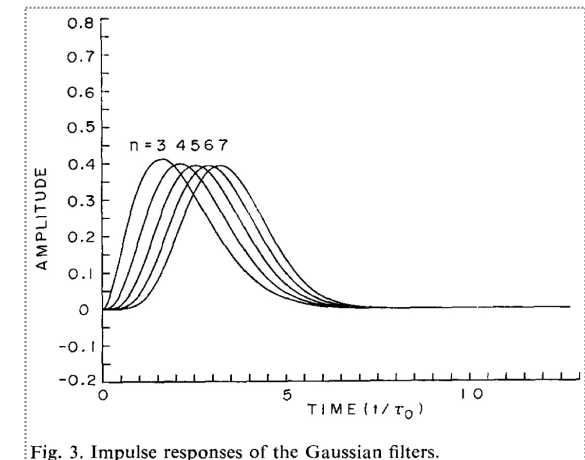


Fig. 3. Impulse responses of the Gaussian filters.

Noise minimization strategy

$$ENC^2 = (C_d + C_{in})^2 \left(A_w v_n^2 \frac{1}{T_p} + A_f K_f \right) + A_p i_n^2 T_p \quad (\text{Sum of white noise, } 1/f \text{ noise and shot noise components})$$

Input stage transistors for A_1 implemented using thick oxide (2.5 V) devices in 65 nm to limit leakage current and associated shot noise

$$ENC_f^2 = K_f \frac{(C_d + C_g)^2}{C_g} N_f \Rightarrow C_g = C_d$$

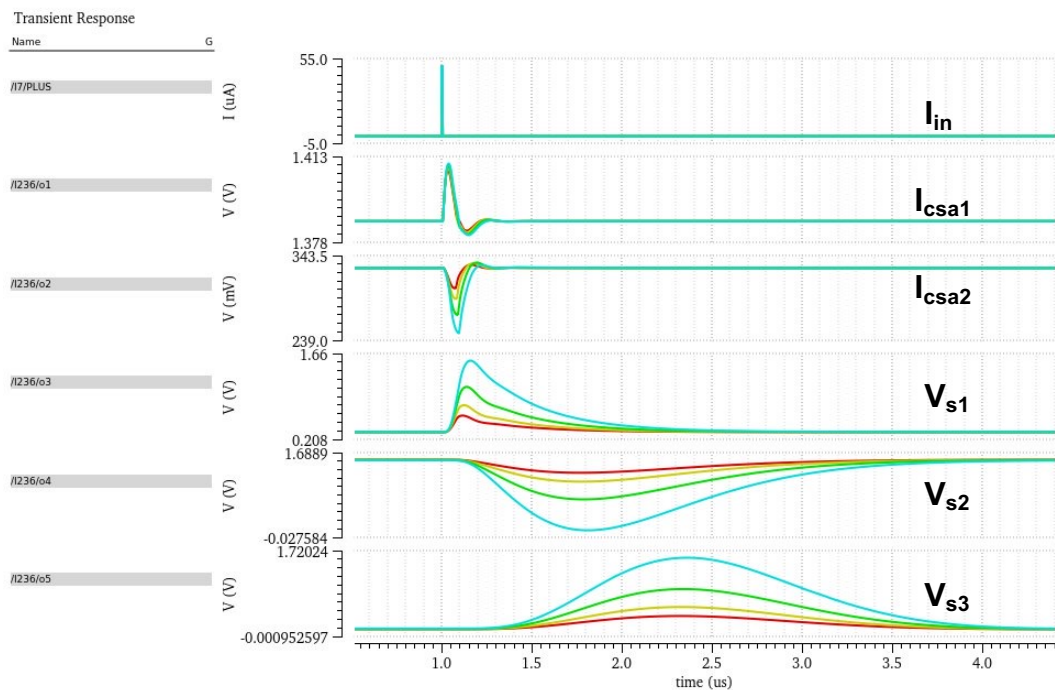
$$ENC_w^2 = 4k_B T n \gamma \alpha_w \frac{(C_d + C_g)^2}{g_m(C_g)} N_f \Rightarrow C_g = \frac{1}{3} C_d$$

Input stage transistor sized to have $C_g \sim 40$ pF, optimal choice for minimizing noise with $C_{det} \sim 150$ pF with given power budget

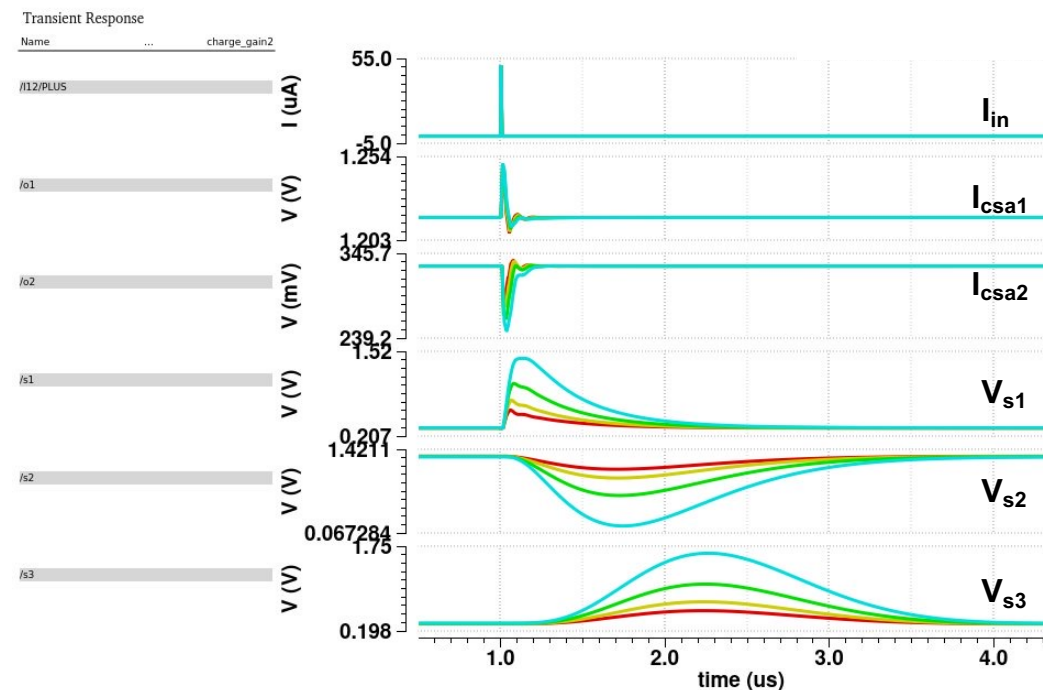
	Minimum allowable transistor length	Input transistor length	Input transistor width
180 nm	180 nm	270 nm	20 mm
65 nm	280 nm	400 nm	24 mm

Transient response : programmable gain

180 nm



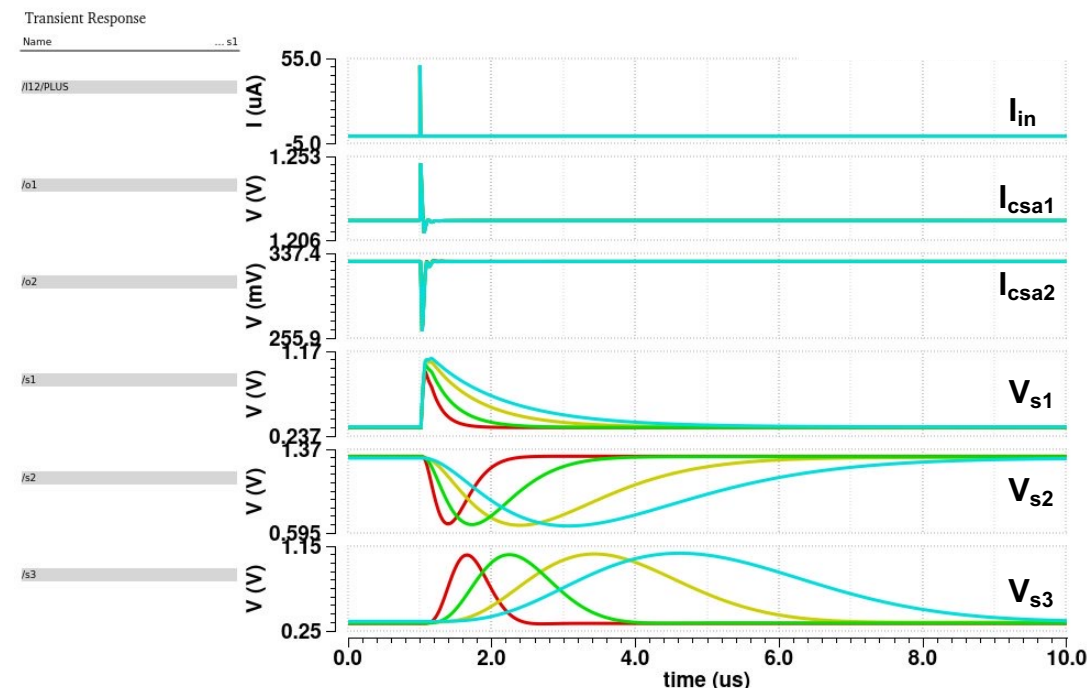
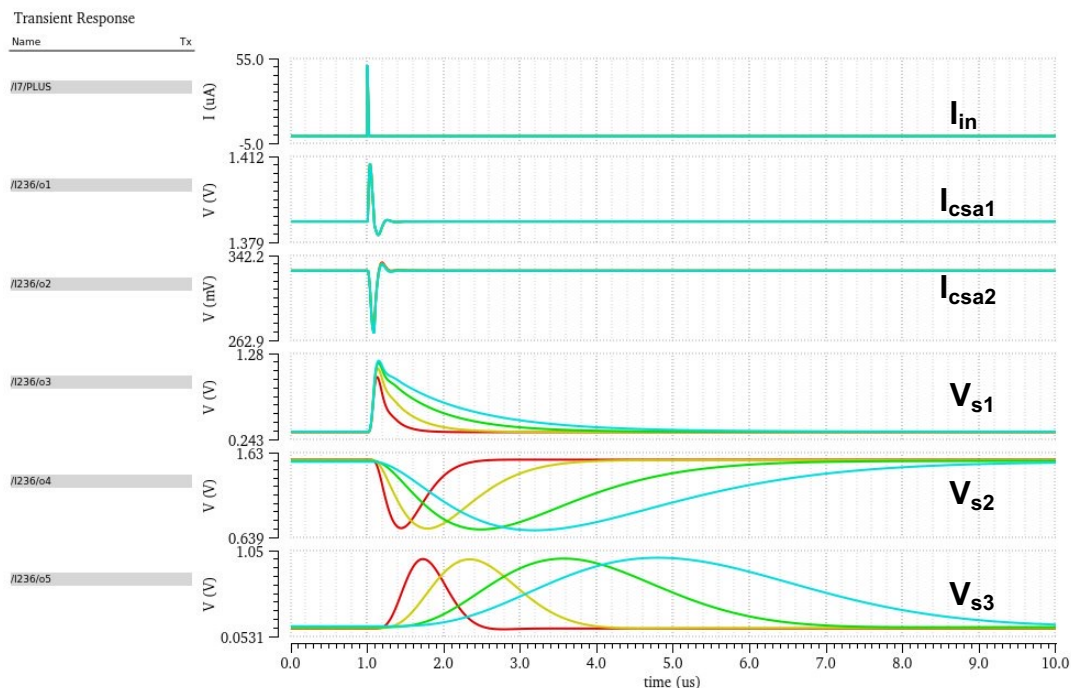
65 nm



Transient response : programmable peaking time

180 nm

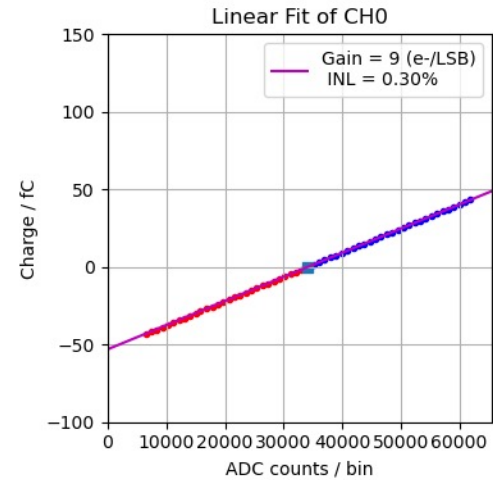
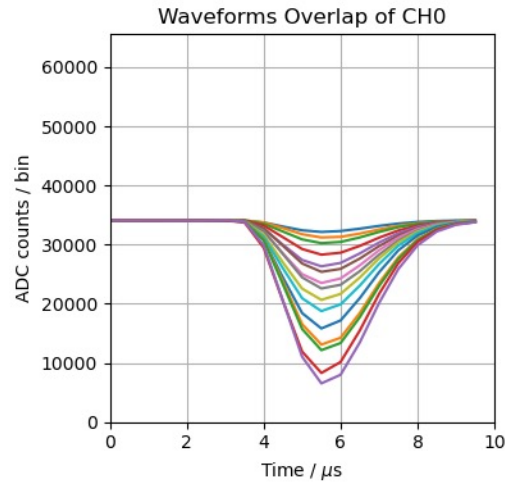
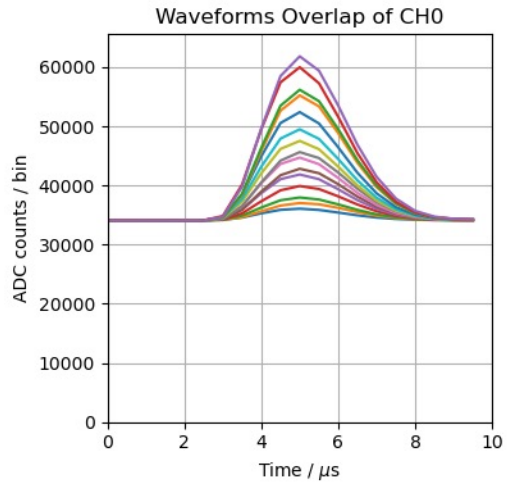
65 nm



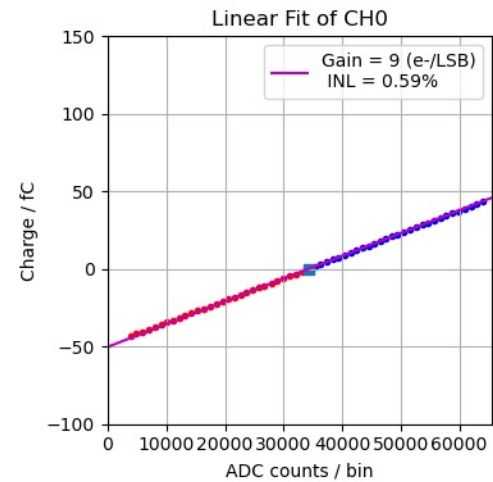
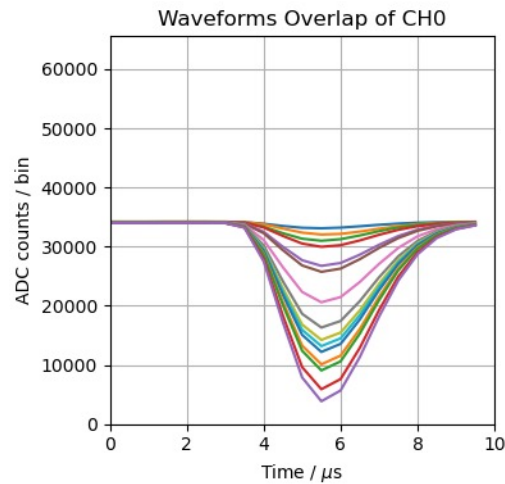
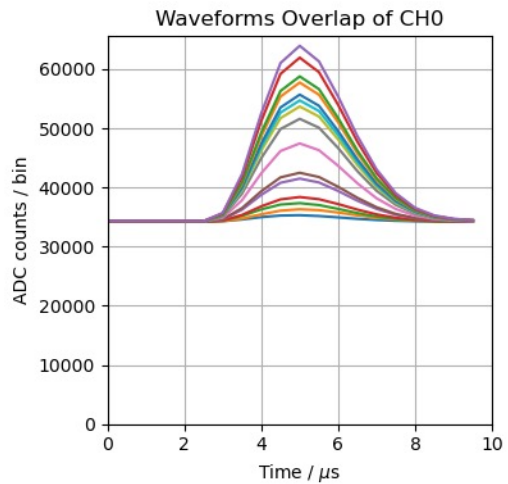
Measured characteristics (P5 – 180 nm)

Charge gain = 9, 900mV baseline, 500pA, $T_p = 2\mu\text{s}$, ADC 16-bit mode

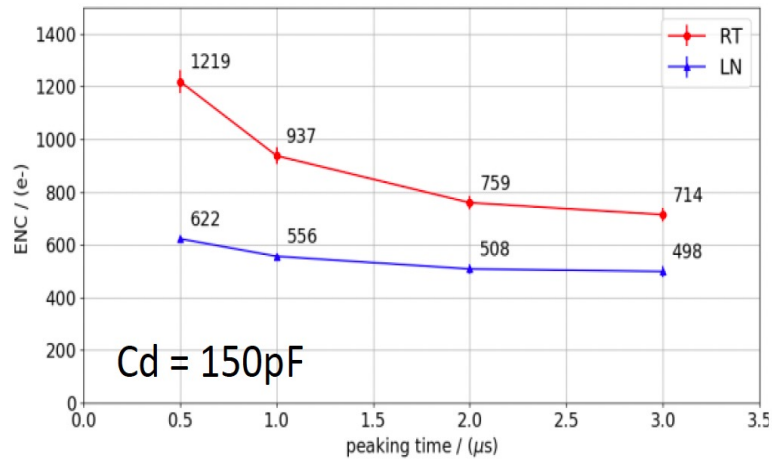
RT



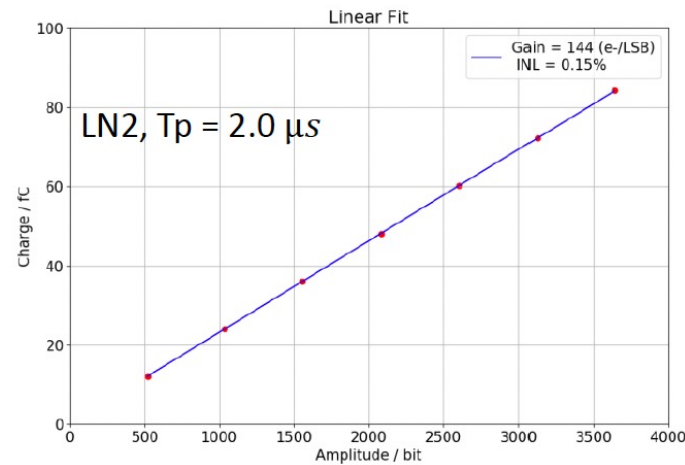
LN2



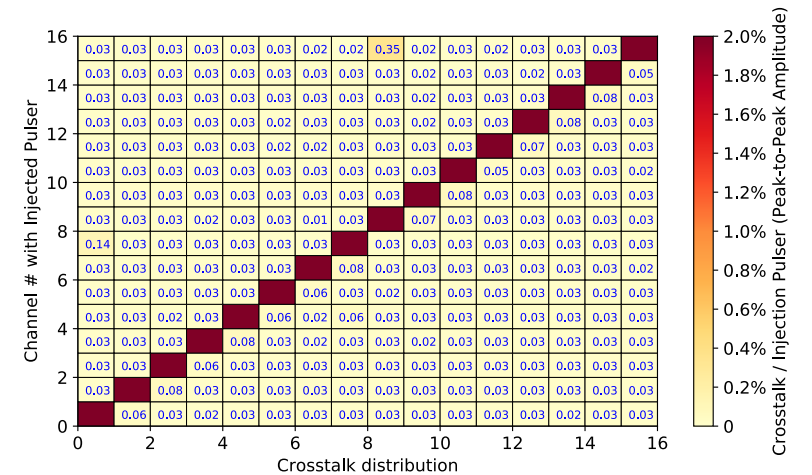
Measured characteristics (P5 – 180 nm)



Low Noise



High Linearity

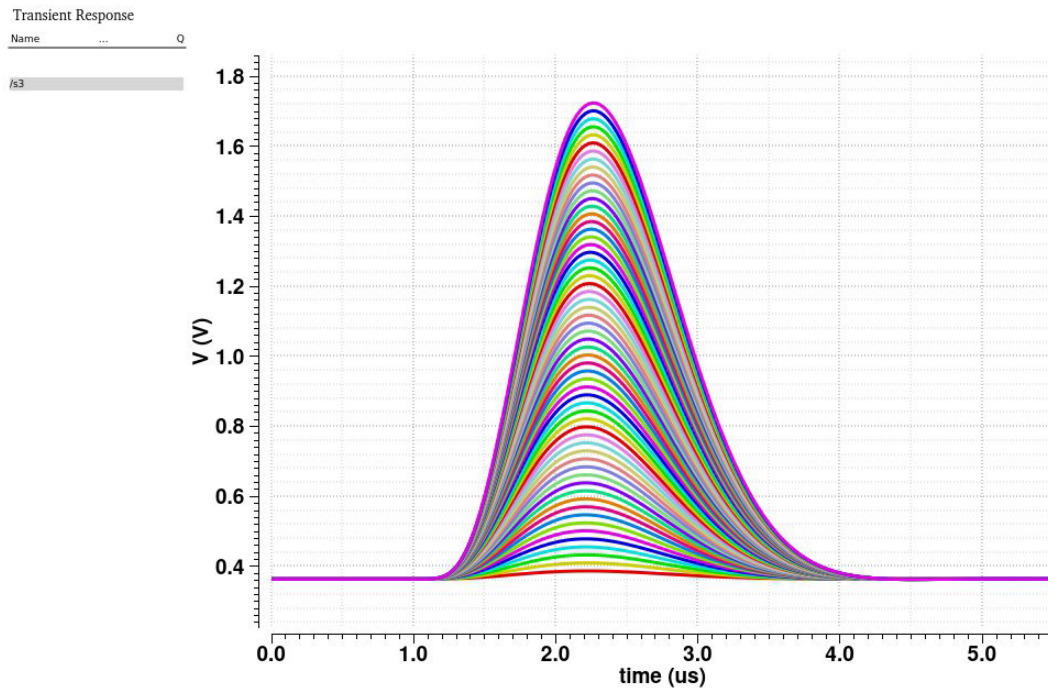


Low Crosstalk

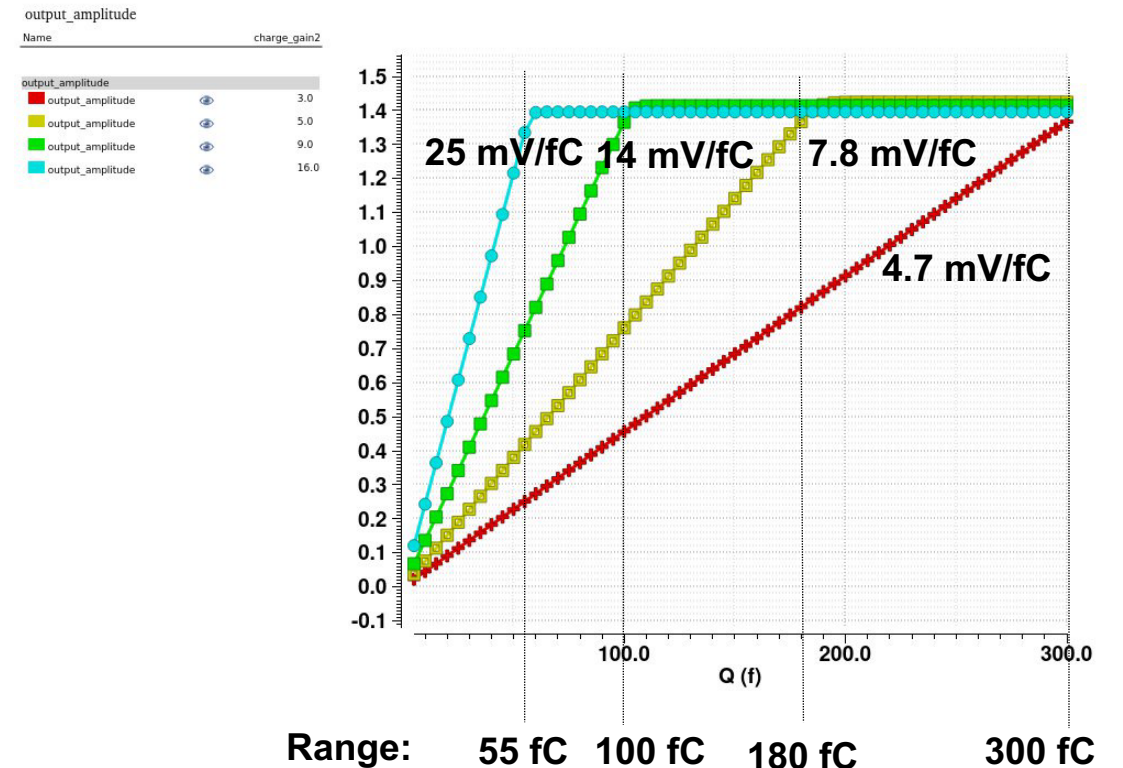
Noise in 65 nm (simulated) is about 10% lower

Linearity characteristics (simulated – 65 nm)

Shaper response for charge gain = 3, $T_p = 1\mu\text{s}$



Output amplitude Vs. input charge



Next Steps

- Fabricating test structures to obtain better $1/f$ noise models in 65 nm
- Fabricating the front-end chain in 65 nm
- Checking what is the shortest shaping time achievable with the current architecture
- Customizing the front-end design for shorter shaping times (~ 20 ns, $C_d \sim 20$ pF) – PIONEER
- Customizing the front-end design to include an on-chip adiabatic capacitor – nEXO (light readout)

Thank you!